

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1588	trench near3 (isolator isolation).ti.	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:29
L2	22863	((trench near3 (isolator isolation)) "STI" 'fox' 'locos') with (opening trench hole recess via groove damascene)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:30
L3	10786	2 and (mask\$3 hard adj mask\$3 hardmask\$3) with (opening trench hole recess via groove damascene)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:38
L5	9670	3 and (substrate) with (opening trench hole recess via groove damascene)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:33
L6	7609	5 and (polishing planar planari\$5 'cmp' chemical adj mechanical)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:35
L8	7587	6 and (etch\$3 remov\$3)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:35
L9	689	8 and (mask\$3 hard adj mask\$3 hardmask\$3) with ("W" tungsten titanium near3 nitride amorphous near2 carbon)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:40
L10	668	9 and (mask\$3 hard adj mask\$3 hardmask\$3"W" tungsten titanium near3 nitride amorphous near2 carbon) with etch\$4	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:41
L11	672	9 and (mask\$3 hard adj mask\$3 hardmask\$3"W" tungsten titanium near3 nitride amorphous near2 carbon) with (remov\$3 etch\$4)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:41

L12	657	9 and (mask\$3 hard adj mask\$3 hardmask\$3"W" tungsten titanium near3 nitride armorphous near2 carbon) near5 (remov\$3 etch\$4)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:43
L13	657	9 and (mask\$3 hard adj mask\$3 hardmask\$3) near5 (remov\$3 etch\$4)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:43

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1588	trench near3 (isolator isolation).ti.	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:29
L2	22863	((trench near3 (isolator isolation)) "STI" 'fox' 'locos') with (opening trench hole recess via groove damascene)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:30
L3	10786	2 and (mask\$3 hard adj mask\$3 hardmask\$3) with (opening trench hole recess via groove damascene)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:38
L5	9670	3 and (substrate) with (opening trench hole recess via groove damascene)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:33
L6	7609	5 and (polishing planar planari\$5 'cmp' chemical adj mechanical)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:35
L8	7587	6 and (etch\$3 remov\$3)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:35
L9	689	8 and (mask\$3 hard adj mask\$3 hardmask\$3) with ("W" tungsten titanium near3 nitride amorphous near2 carbon)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:46
L10	668	9 and (mask\$3 hard adj mask\$3 hardmask\$3"W" tungsten titanium near3 nitride amorphous near2 carbon) with etch\$4	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:41
L11	672	9 and (mask\$3 hard adj mask\$3 hardmask\$3"W" tungsten titanium near3 nitride amorphous near2 carbon) with (remov\$3 etch\$4)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:41

L12	657	9 and (mask\$3 hard adj mask\$3 hardmask\$3"W" tungsten titanium near3 nitride amorphous near2 carbon) near5 (remov\$3 etch\$4)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:43
L13	657	9 and (mask\$3 hard adj mask\$3 hardmask\$3) near5 (remov\$3 etch\$4)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:44
L14	25	1 and 13	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:44
L15	262	13 and (mask\$3 hard adj mask\$3 hardmask\$3) near5 ("W" tungsten titanium near3 nitride amorphous near2 carbon)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:53
L16	153	13 and (mask\$3 hard adj mask\$3 hardmask\$3) near5 (metal\$4)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:48
L17	7285	(mask\$3 hard adj mask\$3 hardmask\$3) near5 ("W" tungsten titanium near3 nitride "TiN" amorphous near2 carbon)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:54
L18	7442	(mask\$3 hard adj mask\$3 hardmask\$3) near5 ("W" tungsten titanium near3 nitride "TiN" amorphous near2 carbon)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:54
L19	6353	(mask\$3 hard adj mask\$3 hardmask\$3) near4 ("W" tungsten titanium near3 nitride "TiN" amorphous near2 carbon)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:54
L20	4957	(mask\$3 hard adj mask\$3 hardmask\$3) near3 ("W" tungsten titanium near3 nitride "TiN" amorphous near2 carbon)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:54

L21	2964	(mask\$3 hard adj mask\$3 hardmask\$3) near2 ("W" tungsten titanium near3 nitride "TiN" amorphous near2 carbon)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:55
L22	18447	(mask\$3 hard adj mask\$3 hardmask\$3) near2 ("W" tungsten titanium near3 nitride "TiN" amorphous near2 carbon metal)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/02 15:55